

Docket Number: 081468-0308270

Client Reference: P-1812.000-US

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re the Application of

DIERICHS

Group Art Unit: 2812

Application No.: 10/775,326

Examiner: Unassigned

Filed: February 11, 2004

Confirmation No.: 8555

For: DEVICE MANUFACTURING METHOD AND A SUBSTRATE

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

Examiner's Initials	First Inventor	Application No.	Filing Date	Enclosed
	DE SMIT (081468-0309173)	10/820,227	04/08/2004	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	DE SMIT (081468-0309978)	10/860,662	06/04/2004	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	DUINEVELD et al. (081468-0308101)	10/773,461	02/09/2004	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	FLAGELLO et al. (081468-0302644)	10/698,012	10/31/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	DE SMIT et al. (081468-0306530)	10/705,804	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	LOF et al. (081468-0306781)	10/705,805	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	LOF et al. (081468-0306524)	10/705,783	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	VAN SANTEN et al. (081468-0307331)	10/743,271	12/23/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	MULKENS et al. (081468-0307333)	10/743,266	12/23/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	DERKSEN et al. (081468-0306526)	10/705,785	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	SIMON et al. (081468-0307087)	10/724,402	12/01/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card

Examiner's Initials	First Inventor	Application No.	Filing Date	Enclosed
	BLEEKER (081468-0306527)	10/715,116	11/18/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	STREEFKERK et al. (081468-0306882)	10/719,683	11/24/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	LOF et al. (081468-0306525)	10/705,816	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	SUWA et al. (Reissue Application of U.S. Patent No. 6,191,429 B1)	10/367,910	02/19/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input type="checkbox"/> Other: stamped receipt card

*The Examiner's initials adjacent a citation indicates he/she has considered the cited application relative to the subject application.

It is respectfully requested that these applications and the art cited therein during examination be expressly considered during the prosecution of this application and be made of record in this application. The identification of the above U.S. patent applications is not to be construed as a waiver of secrecy as to those applications now or upon issuance of the present application as a patent.

PLEASE DO NOT PRINT the above information on the patent which results from this application.

Consideration of each listed application is earnestly solicited since unpublished patent applications are contemplated as IDS material; see the exception in Rule 98(a)(2)(iii) and note the penultimate sentence of MPEP 609.

Further, in keeping with MPEP 609, subsec. C(2), 2nd para., line 10 to end of the paragraph (especially note lines 18-25) **PLEASE RETURN A COPY OF THIS LETTER** with the Examiner's initials adjacent each above listing so that applicant will know that each listed application has been considered as required by PTO policy.

Secondly, please consider each document which is listed on the attached Form PTO-1449 and return a copy of that form with the Examiner's initials adjacent each citation, a copy of each document enclosed except for any U.S. patents and published patent applications. It is respectfully requested that these documents listed on the Form PTO-1449 be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed before the mailing date of the first Office Action on the merits in the present application. No certification or fee is required.

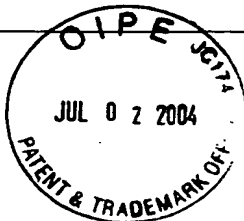
Respectfully Submitted,

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Atty; Dkt. No.	M#	Client Ref.
	308270	P-1812.000-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant:	DIERICH
Appln. No.	10/775,326
Filing Date:	February 11, 2004
Examiner:	Unknown
Group Art Unit:	2812

Date: July 2, 2004 Page 1 of 3

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
	AR 3,573,975	04/1971	DHAKA <i>et al.</i>	117	212	
	BR 3,648,587	03/1972	STEVENS	95	44	
	CR 4,346,164	08/1982	TABARELLI <i>et al.</i>	430	311	
	DR 4,390,273	06/1983	LOEBACH <i>et al.</i>	355	125	
	ER 4,396,705	08/1983	AKEYAMA <i>et al.</i>	430	326	
	FR 4,480,910	11/1984	TAKANASHI <i>et al.</i>	355	30	
	GR 4,509,852	04/1985	Tabarelli <i>et al.</i>	355	30	
	HR 5,040,020	08/1991	RAUSCHENBACH <i>et al.</i>	355	53	
	IR 5,121,256	06/1992	CORLE <i>et al.</i>	359	664	
	JR 5,610,683	03/1997	TAKAHASHI	355	53	
	KR 5,715,039	02/1998	FUKUDA <i>et al.</i>	355	53	
	LR 5,825,043	10/1998	SUWA	250	548	
	MR 5,900,354	05/1999	BATCHELDER	430	395	
	NR 6,191,429	02/2001	SUWA	250	548	

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	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclosed	No
	OR WO 99/49504	09/1999	PCT	Fukami <i>et al.</i>	X		X	
	PR EP 0023231	02/1981	EUROPE	TABARELLI <i>et al.</i>	X			
	QR EP 0418427	03/1991	EUROPE	MIYAKE	X		X	
	RR EP 1039511	09/2000	EUROPE	MURAKIMI <i>et al.</i>	X		X	
	SR DD 224448	07/1985	GERMANY	HESSE <i>et al.</i>		X		
	TR DD 242880	02/1987	GERMANY	KUCH		X		
	UR FR 2474708	07/1981	FRANCE	LETELLIER		X		
	VR JP 62-065326	03/1987	JAPAN	MORIUCHI	X			
	WR JP 62-121417	06/1987	JAPAN	NAKAZAWA	X			
	XR JP 63-157419	06/1988	JAPAN	NAKASUJI	X			
	YR JP 04-305915	10/1992	JAPAN	OZEKI <i>et al.</i>	X			
	ZR JP 04-305917	10/1992	JAPAN	OZEKI <i>et al.</i>	X			
	AAR JP 06-124873	05/1994	JAPAN	TAKAHASHI	X		X	

OTHER (Including in this order: Author, Title, Periodical Name, Date, Pertinent Pages, etc.):

BBR	M. SWITKES <i>et al.</i> , "Immersion Lithography at 157 nm", MIT Lincoln Lab, Orlando 2001-1, December 17, 2001			
CCR	M. SWITKES <i>et al.</i> , "Immersion Lithography at 157 nm", J. Vac. Sci. Technol. B., Vol. 19, No. 6, November/December 2001, pp. 2353-2356			
DDR	M. SWITKES <i>et al.</i> , "Immersion Lithography: Optics for the 50 nm Node", 157 Anvers-1, September 4, 2002			

Examiner: _____ Date Considered: _____

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified) To: U.S. Department of Commerce (PW FORM PAT-1449) Patent and Trademark Office					Atty. Dkt. No.		M#		Client Ref.		
							308270		P-1812.000-US		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT					Applicant: DIERICHS						
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Date: July 2, 2004 Page <u>2</u> of <u>3</u>											
U.S. PATENT DOCUMENTS											
Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)		Class	Sub Class	Filing Date (if appropriate)			
	AR	6,560,032	05/2003	HATANO		359	656				
	BR	6,600,547	07/2003	WATSON <i>et al.</i>							
	CR	6,603,130	08/2003	BISSCHOPS <i>et al.</i>		250	492.1				
	DR	6,633,365	10/2003	SUENAGA		355	53				
	ER	2002/0163629	11/2002	SWITKES <i>et al.</i>		355	53				
	FR	2003/0123040	07/2003	ALMOGY		355	69				
	GR	2003/0174408	09/2003	ROSTALSKI <i>et al.</i>		359	642				
	HR	2004/0000627 A1	01/2004	SCHUSTER							
	IR	2004/0021844 A1	02/2004	SUENAGA							
	JR	2004/0075895 A1	04/2004	LIN		359	380				
	KR	2004/0109237 A1	06/2004	EPPEL <i>et al.</i>							
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		Document Number	Date MM/YYYY	Country	Inventor Name						
						Enclosed	No	Enclosed	No		
	LR	JP 07-220990	08/1995	JAPAN	FUKUDA <i>et al.</i>	X					
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	NR	JP 10-255319	09/1998	JAPAN	SUENAGA <i>et al.</i>	X					
	OR	JP 10-303114	11/1998	JAPAN	SUWA	X			X		
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	QR	JP 2001-091849	04/2001	JAPAN	AIZAKI <i>et al.</i>	X					
	RR	JP 07-132262	05/1995	Japan	HIRAKAWA <i>et al.</i>	X					
	SR	JP 58-202448	11/1983	Japan	KAWAMURA <i>et al.</i>	X					
	TR	WO 04/019128	03/2004	PCT	OMURA <i>et al.</i>	X			X		
	UR	WO 03/077037	09/2003	PCT	ROSTALSKI	X			X		
	VR	WO 03/077036	09/2003	PCT	SCHUSTER	X					
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	WR	B.J. LIN, "Drivers, Prospects and Challenges for Immersion Lithography", TSMC, Inc., September 2002									
	XR	B.J. LIN, "Proximity Printing Through Liquid", IBM Technical Disclosure Bulletin, Vol.20, No. 11B, April 1978, p. 4997									
	YR	B.J. LIN, "The Paths To Subhalf-Micrometer Optical Lithography", SPIE Vol. 922, Optical/Laser Microlithography (1988), pp. 256-269									
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	AAR	S. OWA <i>et al.</i> , "Immersion Lithography; its potential performance and issues", SPIE Microlithography 2003, 5040-186, February 27, 2003									
	BBR	S. OWA <i>et al.</i> , "Advantage and Feasibility of Immersion Lithography", Proc. SPIE 5040 (2003)									
Examiner						Date Considered:					
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FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
						Enclosed	No	Enclosed	No
	DR	DD 206 607	02/1984	GERMANY	WESTPHAL et al.		X		
	ER	DD 221 563	04/1985	GERMANY	PFORR et al.		X		
	FR	JP 11-176727	07/1999	JAPAN	SHIRAIISHI	X			
	GR								

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	IR	H. KAWATA et al., "Optical Projection Lithography using Lenses with Numerical Apertures Greater than Unity", Microelectronic Engineering 9 (1989), pp. 31-36							
	JR	J.A. HOFFNAGLE et al., "Liquid Immersion Deep-Ultraviolet Interferometric Lithography", J. Vac. Sci. Technol. B., Vol. 17, No. 6, November/December 1999, pp. 3306-3309							
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	OR	S. OWA and N. NAGASAKA, "Potential Performance and Feasibility of Immersion Lithography", NGL Workshop 2003, July 10, 2003, Slide Nos. 1-33.							
	PR	S. OWA et al., "Update on 193nm immersion exposure tool", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-51							
	QR	H. HATA, "The Development of Immersion Exposure Tools", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-22							
	RR	T. MATSUYAMA et al., "Nikon Projection Lens Update", SPIE Microlithography 2004, 5377-65, March, 2004							
	SR	"Depth-of-Focus Enhancement Using High Refractive Index Layer on the Imaging Layer", IBM Technical Disclosure Bulletin, Vol. 27, No. 11, April 1985, p. 6521							
	TR	A. SUZUKI, "Lithography Advances on Multiple Fronts", EEdesign, EE Times, January 5, 2004							
	UR	B. LIN, "The k_3 coefficient in nonparaxial λ /NA scaling equations for resolution, depth of focus, and immersion lithography, J. Microlith., Microfab., Microsyst. 1(1):7-12 (2002)							
	VR								

Examiner

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